

PACKAGED SURFACE ACOUSTIC WAVE DEVICES

CROSS REFERENCE TO PRIORITY APPLICATIONS

[0001] Any and all applications for which a foreign or domestic priority claim is identified in the Application Data Sheet as filed with the present application are hereby incorporated by reference under 37 C.F.R. § 1.57. This application claims the benefit of priority under 35 U.S.C. § 119(e) of U.S. Provisional Application No. 62/725,133, filed August 30, 2018 and entitled “PACKAGED SURFACE ACOUSTIC WAVE DEVICES,” the disclosure of which is hereby incorporated by reference in its entirety.

BACKGROUND

Technical Field

[0002] Embodiments of this disclosure relate to packaged surface acoustic wave devices.

Description of Related Technology

[0003] A surface acoustic wave filter can include a plurality of surface acoustic wave resonators arranged to filter a radio frequency signal. Each resonator can include a surface acoustic wave device. Surface acoustic wave filters can be implemented in radio frequency electronic systems. For instance, filters in a radio frequency front end of a mobile phone can include surface acoustic wave filters. A plurality of acoustic wave filters can be arranged as a multiplexer. For example, two surface acoustic wave filters can be arranged as a duplexer.

[0004] Surface acoustic wave devices can be enclosed within a package to protect the surface acoustic wave devices. The package can add to the size of a packaged surface acoustic wave device. There is a desire for smaller and thinner packaged surface acoustic wave devices.

SUMMARY OF CERTAIN INVENTIVE ASPECTS

[0005] The innovations described in the claims each have several aspects, no single one of which is solely responsible for its desirable attributes. Without limiting the

scope of the claims, some prominent features of this disclosure will now be briefly described.

[0006] One aspect of this disclosure is a packaged surface acoustic wave device. The packaged surface acoustic wave device includes a cavity roof over an interdigital transducer electrode of a surface acoustic wave device, a conductive structure over the cavity roof, and a photosensitive buffer coat layer over the conductive structure, the packaged surface acoustic wave device having a height of 220 micrometers or less.

[0007] The packaged surface acoustic wave device can have a height of 200 micrometers or less. The photosensitive buffer coat layer can have a height of 15 micrometers or less.

[0008] The packaged surface acoustic wave device can further include a piezoelectric substrate having a first side on which the interdigital transducer electrode is disposed, and a cavity wall on the first side of the piezoelectric substrate and supporting the cavity roof. An edge portion of the first side of the piezoelectric substrate can be free from the photosensitive buffer coat layer.

[0009] The packaged surface acoustic wave device can further include a piezoelectric substrate having a first side and a second side opposite the first side, the interdigital transducer electrode being on the first side, and a marking extending into the second side, the marking extending 1 micrometer or less into the piezoelectric substrate. The packaged surface acoustic wave device of claim 1 can further include a terminal in physical contact with the conductive structure through an opening in the photosensitive buffer coat layer.

[0010] The photosensitive buffer coat layer can include phenol resin. The photosensitive buffer coat layer can have a negative photosensitivity.

[0011] The surface acoustic wave device can include a plurality of surface acoustic wave resonators configured to filter a radio frequency signal.

[0012] Another aspect of this disclosure is a packaged surface acoustic wave device that includes a cavity structure supported by a die and cooperating the die to encapsulate an interdigital transducer electrode of a surface acoustic wave device, a conductive structure extending over a portion of an outer surface of the cavity structure, and an insulating layer extending over the conductive structure, a portion of the insulating layer overlying a portion of the conductive structure having a thickness of less than 15 micrometers.

[0013] The cavity structure can include a cavity wall supported by a first surface of the die and a cavity roof extending over the interdigital transducer electrode and supported by the cavity wall. The packaged surface acoustic wave device can further include a plurality of terminals, each of the terminals extending through a portion of the insulating layer and contacting a portion of the conductive structure.

[0014] The insulating layer can include a photoresist material. The insulating layer can include a negative photoresist.

[0015] The die can include a laser-marked piezoelectric substrate having a first side and a second side, the first side supporting the cavity structure, the second side of the laser-marked piezoelectric substrate having a laser-marked section.

[0016] Another aspect of this disclosure is a packaged surface acoustic wave device that includes a piezoelectric substrate, a packaging structure supported by a first surface of the piezoelectric substrate and defining a cavity, the packaging structure including an outer layer including photosensitive resin, and a plurality of interdigital transducer electrodes supported by the piezoelectric substrate and located within the cavity.

[0017] The packaging structure can include a cavity roof and a cavity wall, the cavity roof and the cavity wall both located between a portion of the outer layer and the plurality of interdigital transducer electrodes.

[0018] The packaging structure can include a conductive structure in electrical communication with at least one of the plurality of interdigital transducer electrodes. The packaging structure can include at least one terminal overlying a portion of the outer layer and extending through a portion of the outer layer to contact the conductive structure.

[0019] Another aspect of this disclosure is a method of manufacturing a packaged surface acoustic wave device, the method including forming a photosensitive resin over a conductive structure, a portion of the conductive structure located over a cavity roof over an interdigital transducer electrode of the surface acoustic wave device, and forming a conductive terminal in contact with the conductive structure, at least a portion of the conductive terminal extending through an aperture extending through the photosensitive resin.

[0020] The method can additionally include exposing portions of the photosensitive resin to light to develop portions of the photosensitive resin and removing unexposed portions of the photosensitive resin. The method can additionally include

curing the photosensitive resin after removing unexposed portions of the photosensitive resin. Exposing portions of the photosensitive resin to light can include masking a portion of the photosensitive resin extending over a portion of the conductive structure to form the aperture extending through the photosensitive resin.

[0021] Forming the terminal can additionally include forming a conductive layer extending over the aperture extending through the photosensitive resin. The aperture can extend through a portion of the photosensitive resin having a thickness of 15 micrometers or less.

[0022] The photosensitive resin can include phenol resin. The photosensitive resin can have a negative photosensitivity.

[0023] The can additionally include laser marking a piezoelectric substrate on which the interdigital transducer electrode is disposed.

[0024] The packaged surface acoustic wave device can have a height of less than 220 micrometers.

[0025] Another aspect of this disclosure is a method of manufacturing a packaged surface acoustic wave device, the method including forming a cavity structure encapsulating interdigital transducer electrodes of a surface acoustic wave device, the interdigital transducer electrodes supported by a piezoelectric substrate, forming a conductive structure extending over portions of an outer surface of the cavity structure, and forming a photoresist layer over the conductive structure, a portion of the photoresist layer extending over a portion of the conductive structure having a thickness of less than 15 micrometers.

[0026] The method can additionally include patterning the photoresist layer to form a photoresist buffer coat extending over the conductive structure and the cavity structure and curing the photoresist layer. The photoresist buffer coat can include a sidewall portion in contact with the piezoelectric substrate and circumscribing the cavity structure. A portion of the conductive structure can be in contact with the piezoelectric substrate.

[0027] Forming the photoresist layer over the conductive structure can include using a spin-on process to planarize the photoresist layer. The method can additionally include removing portions of the photoresist layer within 10 micrometers of the edge of the die.

[0028] Another aspect of this disclosure is a method of manufacturing a packaged surface acoustic wave device, the method including forming a cavity structure extending over interdigital transducer electrodes of the surface acoustic wave device, and forming a conductive structure extending over portions of an outer surface of the cavity structure, and forming a photosensitive resin layer over the conductive structure, a portion of the photosensitive resin layer having an aperture extending therethrough and exposing a portion of the conductive structure.

[0029] Forming the conductive structure can include depositing a seed layer over the cavity structure and plating the conductive structure onto the seed layer. Forming the conductive structure further can include masking portions of the seed layer prior to plating the conductive structure onto the seed layer.

[0030] The conductive structure can include a gap extending through a portion thereof and exposing a portion of the cavity structure, and the photosensitive resin layer can fill the gap. The method can additionally include forming a conductive terminal extending through an aperture in the photosensitive resin layer and in electrical communication with the conductive structure.

[0031] Another aspect of this disclosure is a packaged surface acoustic wave device that includes a piezoelectric substrate having a first side and a second side, an interdigital transducer electrode encapsulated within a package structure and supported by the first side of the piezoelectric substrate, and a marking formed in the second side of the piezoelectric substrate.

[0032] The marking can extend less than 1 micrometer into the second side of the piezoelectric substrate. The marking can extend into less than 1% of a thickness of the piezoelectric substrate. The marking can be formed by a laser.

[0033] The piezoelectric substrate can include lithium niobate. The piezoelectric substrate can include lithium tantalite.

[0034] The package structure can include a cavity structure encapsulating the interdigital transducer electrode and an outer coat including a photosensitive resin. A total thickness of the packaged surface acoustic wave device can be less than 220 micrometers.

[0035] The package structure can include a photosensitive resin buffer coat. The photosensitive resin buffer coat can include phenol resin. The photosensitive resin buffer coat can include a negative photoresist. The packaged surface acoustic wave

device can additionally include a plurality of terminals extending through apertures in the photosensitive resin buffer coat.

[0036] Another aspect of this disclosure is a packaged surface acoustic wave device that includes a laser-marked piezoelectric substrate having a first side and a second side, the second side of the laser-marked piezoelectric substrate having a laser-marked section, an interdigital transducer electrode supported by the first side of the laser marked piezoelectric substrate, and a structure supported by the first side of the laser-marked piezoelectric substrate defining a cavity enclosing the interdigital transducer electrode.

[0037] The laser-marked section can have been exposed to a deep ultraviolet laser. The laser-marked section can include laser markings extending less than 1 micrometer into the second side of the piezoelectric substrate.

[0038] The laser-marked piezoelectric substrate can include lithium niobate. The laser-marked piezoelectric substrate can include lithium tantalite.

[0039] The package structure can include a photosensitive resin buffer coat. The photosensitive resin buffer coat can include phenol resin. The photosensitive resin buffer coat can include a negative photoresist. Another aspect of this disclosure is a method of marking a packaged surface acoustic wave device, the method including grinding a back side of a piezoelectric substrate, the back side being opposite a front side of the piezoelectric substrate on which an interdigital transducer electrode of the surface acoustic wave device is disposed, and laser marking the piezoelectric substrate.

[0040] The laser marking can form a marking that extends less than 1 micron into the piezoelectric substrate. The laser marking includes can include a wavelength of laser light that allows the piezoelectric substrate to maintain structural integrity.

[0041] The laser marking can include using a deep ultraviolet laser. The laser marking can include using a laser with a wavelength of about 266 nanometers.

[0042] Grinding the back side of the piezoelectric substrate can include grinding the back side of the piezoelectric substrate until a thickness of the piezoelectric substrate is about 130 micrometers.

[0043] The piezoelectric substrate can include lithium niobate. The method of claim 62 where the piezoelectric substrate can include lithium tantalite.

[0044] The method can additionally include forming a structure supported by the front side of the piezoelectric substrate and defining a cavity enclosing the interdigital

transducer electrode. The structure supported by the front side of the piezoelectric substrate can be formed before grinding the back side of the piezoelectric substrate. Forming the structure supported by the front side of the piezoelectric substrate can include forming a photosensitive resin buffer coat.

[0045] Another aspect of this disclosure is a method of marking a packaged surface acoustic wave device, the method including forming a packaging structure on a first surface of a piezoelectric substrate on which an interdigital transducer electrode of the surface acoustic wave device is disposed, the packaging structure encapsulating the interdigital transducer electrode in a cavity, and directly marking a second surface of the piezoelectric substrate to form a marked portion of the piezoelectric substrate.

[0046] Directly marking the second surface of the piezoelectric substrate can include exposing the marked portion of the second surface of the piezoelectric substrate to laser light. The laser light can include deep ultraviolet light. The laser light can have a wavelength of about 266 nanometers.

[0047] Forming a packaging structure can include forming a layer of photosensitive resin and patterning the layer of photosensitive resin. The photosensitive resin can include a phenol resin. Forming a packaging structure can include forming a conductive terminal extending through the layer of photosensitive resin.

[0048] The marking can extend less than 1 micron into the piezoelectric substrate. The packaged surface acoustic wave device can have a thickness of less than 220 micrometers.

[0049] Another aspect of this disclosure is a packaged surface acoustic wave device that includes a cavity roof over interdigital transducers of a surface acoustic wave device, a plate over the cavity roof, and a photosensitive buffer coat layer over the plate, the packaged surface acoustic wave device having a height of 220 micrometers or less.

[0050] The packaged surface acoustic wave device can have a height of 200 micrometers or less. The photosensitive buffer coat layer can have a height of 15 micrometers or less.

[0051] The packaged surface acoustic wave device can additionally include a piezoelectric substrate having a first side on which the interdigital transducers are disposed, an edge portion of the first side of the piezoelectric substrate can be free from the photosensitive buffer coat layer.

[0052] The packaged surface acoustic wave device can additionally include a piezoelectric substrate having a first side and a second side opposite the first side, the interdigital transducers can be on the first side, and marking can extend into the second side. The marking can extend 1 micrometer or less into the piezoelectric substrate.

[0053] The packaged surface acoustic wave device can additionally include a terminal in physical contact with the plate though an opening in the photosensitive buffer coat layer.

[0054] The photosensitive buffer coat layer can include phenol resin. The photosensitive buffer coat layer can have a negative photosensitivity.

[0055] The packaged surface acoustic wave device can include a surface acoustic wave device configured to filter a radio frequency signal.

[0056] Another aspect of this disclosure is a packaged surface acoustic wave device that includes a piezoelectric substrate having a first side and a second side opposite the first side, the second side having markings extending therein, a cavity roof over interdigital transducers of the surface acoustic wave device on the first side of the piezoelectric substrate, a plate over the cavity roof, and an insulating layer over the plate.

[0057] Another aspect of this disclosure is a packaged surface acoustic wave device that includes a piezoelectric substrate, a cavity roof over interdigital transducers of the surface acoustic wave device, the interdigital transducers being disposed on the piezoelectric substrate, a plate over the cavity roof, and an insulating layer over the plate, an edge portion of the piezoelectric substrate being free from the insulating layer.

[0058] Another aspect of this disclosure is a packaged surface acoustic wave device that includes a cavity roof over interdigital transducers of a surface acoustic wave device, a plate over the cavity roof, and an insulating layer over the plate, the insulating layer having a thickness of 10 micrometers or less, and the packaged surface acoustic wave device having a height of 200 micrometers or less.

[0059] Another aspect of this disclosure is a method of manufacturing a packaged surface acoustic wave device, the method including forming a photosensitive resin over a plate, the plate being positioned over a cavity roof enclosing interdigital transducers of the surface acoustic wave device, and forming a terminal of the surface acoustic wave device over the photosensitive resin such that the terminal is in contact with the plate.

[0060] The method can additionally include exposing portions of the photosensitive resin to light and making other portions of the photosensitive resin to provide an opening through the photosensitive resin, where forming the terminal can include filling the opening with material of the terminal.

[0061] The method can additionally include exposing the photosensitive resin to light and making other portions of the photosensitive resin to provide an edge of a piezoelectric substrate free from the photosensitive resin, and the interdigital transducer electrodes can be positioned on the piezoelectric substrate.

[0062] The photosensitive resin can have a thickness of 15 micrometers or less. The photosensitive resin can include phenol resin.

[0063] The method can additionally include laser marking a piezoelectric substrate on which the interdigital transducers are disposed.

[0064] Another aspect of this disclosure is a method of marking a packaged surface acoustic wave device, the method including grinding a back side of a piezoelectric substrate, the back side being opposite a front side of the piezoelectric substrate on which interdigital transducers of the surface acoustic wave device are disposed, and laser marking the piezoelectric substrate.

[0065] The marking can extend less than 1 micron into the piezoelectric substrate.

[0066] The laser marking can include applying a wavelength of laser light that allows the piezoelectric substrate to maintain structural integrity. The laser marking can include using a deep ultraviolet laser.

[0067] For purposes of summarizing the disclosure, certain aspects, advantages and novel features of the innovations have been described herein. It is to be understood that not necessarily all such advantages may be achieved in accordance with any particular embodiment. Thus, the innovations may be embodied or carried out in a manner that achieves or optimizes one advantage or group of advantages as taught herein without necessarily achieving other advantages as may be taught or suggested herein.

BRIEF DESCRIPTION OF THE DRAWINGS

[0068] Embodiments of this disclosure will now be described, by way of non-limiting example, with reference to the accompanying drawings.

[0069] **Figure 1** is a cross sectional diagram of a packaged surface acoustic wave device according to an embodiment.

[0070] **Figure 2A** is another cross section diagram of a packaged surface acoustic wave device according to another embodiment. **Figure 2B** is a detailed view of section **B** of **Figure 2A**.

[0071] **Figures 3A–3J** are cross-sections of a portion of a packaged surface acoustic wave device at various stages of a manufacturing process according to an embodiment.

[0072] **Figures 4A–4F** are cross-sections of a portion of a partially packaged surface acoustic wave device at various stages of a manufacturing process including multiple photoresist exposures according to another embodiment.

[0073] **Figures 5A–5E** are cross-sections of a portion of a partially packaged surface acoustic wave device at various stages of a manufacturing process including a plating process according to another embodiment.

[0074] **Figures 6A–6C** are cross-sections of a portion of a partially packaged surface acoustic wave device at various stages of a manufacturing process including a spin-coating process according to another embodiment.

[0075] **Figure 7** is a flow diagram of a process of manufacturing a packaged surface acoustic wave device including a photosensitive buffer coat according to an embodiment.

[0076] **Figure 8** is a flow diagram of a process of manufacturing a packaged surface acoustic wave device including laser marking of a piezoelectric layer according to an embodiment.

[0077] **Figure 9** is a schematic diagram of a radio frequency module that includes a filter with SAW resonators according to an embodiment.

[0078] **Figure 10** is a schematic diagram of a radio frequency module that includes duplexers with surface acoustic wave resonators according to an embodiment.

[0079] **Figure 11** is a schematic block diagram of a module that includes a power amplifier, a radio frequency switch, and duplexers that include one or more surface acoustic wave resonators according to an embodiment.

[0080] **Figure 12** is a schematic block diagram of a module that includes a low noise amplifier, a radio frequency switch, and surface acoustic wave filters according to an embodiment.

[0081] **Figure 13** is a schematic block diagram of a module that includes an antenna switch and duplexers that include one or more surface acoustic wave resonators according to an embodiment.

[0082] **Figure 14** is a schematic block diagram of a wireless communication device that includes a surface acoustic wave filter in accordance with one or more embodiments.

[0083] **Figure 15** is a schematic block diagram of another wireless communication device that includes a surface acoustic wave filter in accordance with one or more embodiments.

DETAILED DESCRIPTION OF CERTAIN EMBODIMENTS

[0084] The following description of certain embodiments presents various descriptions of specific embodiments. However, the innovations described herein can be embodied in a multitude of different ways, for example, as defined and covered by the claims. In this description, reference is made to the drawings where like reference numerals can indicate identical or functionally similar elements. It will be understood that elements illustrated in the figures are not necessarily drawn to scale. Moreover, it will be understood that certain embodiments can include more elements than illustrated in a drawing and/or a subset of the elements illustrated in a drawing. Further, some embodiments can incorporate any suitable combination of features from two or more drawings.

[0085] As the semiconductor market becomes increasingly competitive, there are more demands for smaller and thinner packaged surface acoustic wave devices. For instance, in certain applications, specifications call for surface acoustic wave device package heights of 200 microns or less so that the packaged surface acoustic wave devices can fit into a module. Methods of packaging are disclosed can achieve lower profile and lower cost for a package of a surface acoustic wave device. Surface acoustic wave devices with Wafer Level Chip Scale Packaging (WL-CSP) for surface acoustic wave filters with thinner packages are disclosed.

[0086] Methods of packaging surface acoustic wave devices are disclosed to reduce package height and/or lower packaging costs. Package structures disclosed herein include a photosensitive buffer coat layer, which acts as a protective layer covering a copper (Cu) plating. With a thin photosensitive buffer coat layer, the package structure can be formed without a post structure connecting a terminal to internal conductive structures of the package. Package structures disclosed herein include marking on a piezoelectric substrate of a surface acoustic wave device. A laser can mark the piezoelectric substrate without damaging the functionality of the piezoelectric substrate. Package structures disclosed herein can meet electrical performance and moldability strength specifications. The packaged surface acoustic wave devices disclosed herein can include surface acoustic wave filters arranged to filter radio frequency signals.

[0087] **Figure 1** is a cross sectional diagram of a packaged surface acoustic wave device according to an embodiment. Certain aspects of the packaged surface acoustic wave device **100** allow the thickness of the package to be reduced. For example, the packaged surface acoustic wave device **100** can have a package height H_1 of less than 220 micrometers (um). In certain embodiments, the package height H_1 can be less than 200 um. In one exemplary embodiment, the packaged surface acoustic wave device **100** has a package height H_1 of approximately 190 um.

[0088] As illustrated in **Figure 1**, the packaged surface acoustic wave device **100** includes a die **102**, and interdigital transducer electrodes **104** on the die **102**. The die **102** is a piezoelectric substrate. The die **102** can include a lithium-containing piezoelectric material, such as a lithium niobate or lithium tantalate, for example. In some instances, the die **102** includes a multi-layer piezoelectric substrate. The die **102** can be approximately 130 um tall in certain instances. Other suitable thicknesses may also be used in other embodiments.

[0089] The die **102** can include a marked section **108** on a side of the die **102** opposite the interdigital transducer electrodes **104**. The marked section **108** can be relatively shallow, compared to the overall thickness of the die **102**. In some embodiments, the markings of the marked section **108** can extend less than 1 um into the die. By marking directly into the die **102**, no additional marking film is included in the packaged surface acoustic wave device **100** of **Figure 1**. This can reduce the overall height of the packaged surface acoustic wave device **100** relative to packaged surface acoustic wave devices that include marking films.

[0090] Interdigital transducer electrodes **104** of surface acoustic wave resonators are disposed on the die **102**. The surface acoustic wave resonators can be arranged as a filter configured to filter a radio frequency signal. Any suitable number of surface acoustic wave resonators and/or surface acoustic wave filters can be included in the packaged surface acoustic wave device **100**.

[0091] The interdigital transducer electrodes **104** are disposed within a cavity **116**. The sides of the cavity **116** are formed by cavity walls **112** supported by the die **102**. The roof of the cavity **116** is formed by a cavity roof **114** supported by the cavity walls **112** and extending over the interdigital transducer electrodes **104**. The cavity **116** may be an air cavity. In some embodiments, the cavity **116** may be about 25 um tall, although other suitable cavity heights may also be used.

[0092] In some embodiments, one or both of the cavity roof **114** and the cavity walls **112** may include a photoresist material, as discussed in greater detail below.

[0093] Portions of the outer surfaces of the cavity roof **114** and the cavity walls **112** are covered by a conductive layer **122**. In some embodiments, the conductive layer **122** may be formed by covering the outer surfaces of the cavity roof **114** and the cavity walls **112** with a seed layer, and then forming the conductive layer **122** over the seed layer using a plating process. The conductive layer **122** may include more than one section, which may be electrically isolated from one another by at least one gap **124** in the conductive layer **122**. The conductive layer **122** may be about 25 um in thickness in certain embodiments, although other suitable thicknesses may also be used.

[0094] In some embodiments, the conductive layer **122** includes a layer of copper which is plated onto a seed layer including copper and/or titanium.

[0095] The conductive layer **122** may extend along the sides of the cavity walls **112**, and down to the die **102**, where the conductive layer **122** may contact interconnect structures such as electronic traces on the die **102**, allowing electrical communication with the interdigital transducer electrodes **104** of surface acoustic wave resonator structures within the packaged surface acoustic wave device **100**. The conductive layer **122** can be referred to as a plate layer in certain applications.

[0096] An insulation layer **132** extends over outer surfaces of the conductive layer **122**, and fills the gap **124** in the conductive layer **122**. Side portions **136** of the insulation layer **132** extend down the sides of the conductive layer **122** to the die **102**. In certain embodiments, the insulation layer **132** is a photosensitive resin. In some

embodiments, the conductive layer **122** may be a negative photoresist. In some embodiments, the photosensitive resin can be a phenol resin with rubber filler. Such a resin may have a viscosity of about 700 centipoise (cP), and may have a shelf life of about 9 months at 5°C, and a floor life of about 4 months. The cured resin may have a Young's modulus of elasticity of about 2.2 gigapascals (GPa), and a coefficient of thermal expansion of roughly 55/°C.

[0097] The insulation layer **132** can be made relatively thin. In some embodiments, the insulation layer may be about 15 μm thick or less. In some embodiments, the thickness of an insulation layer **132** including phenol resin with rubber filler can be in a range from about 6 μm to about 14 μm . In some particular embodiments, the thickness of an insulation layer **132** including phenol resin with rubber filler may be about 10 μm . The formation of the insulation layer **132** using a material such as the photosensitive resin can reduce the overall height of the packaged surface acoustic wave device **100** relative to other devices with thicker insulation layers.

[0098] In addition to the reduction in thickness, a photosensitive buffer coat layer as an insulation layer **132** can be removed to provide no significant residue on other portions of the die **102**, such as the opening and saw street area where die are diced and singulated. The use of photosensitive buffer coat layer can also provide good coverage on the surfaces of a copper conductive layer, without significant copper oxidation after buffer coat curing. A photosensitive buffer coat layer can also pass ball shear and reliability tests.

[0099] The insulation layer **132** can be a photosensitive buffer coat layer. In some embodiments, negative-type photosensitive material can be used as the photosensitive buffer coat layer. The photosensitive buffer coat layer can be thicker at the saw street at the edge of the device, due to the trench made by the height of the cavity wall, cavity roof, and conductive layer. For positive-type photosensitive material, where the area of the photosensitive material to be removed is exposed to light, and exposure energy can be a significant factor in removing residue. A relatively high exposure dose can be applied in order to develop positive-type photosensitive material, to penetrate the relatively thick buffer coat at the edge of the device. This can make it difficult to develop positive material when exposure energy is not sufficiently high. With relatively high exposure energy, there can be thinning of the edges close to the saw street.

[0100] In contrast, for negative-type photosensitive material, the area of the photosensitive buffer intended to remain in the finished device is exposed to light. The development rate can depend on the properties of the photosensitive material. A negative-type photosensitive material can be easily developed at the saw street area at the side of the packaged surface acoustic wave device.

[0101] The packaged surface acoustic wave device **100** also includes terminals **142a** and **142b** located above respective portions of the conductive layer **122** and in physical contact with the conductive layer **122** through apertures in the insulation layer **132**. Portions **144a** and **144b** of terminals **142a** and **142b**, respectively, extend through the apertures in the insulation layer **132**. Solder layers **146a** and **146b** overlie the terminals **142a** and **142b**, respectively.

[0102] A conformal layer overlying the patterned insulation layer **132** can form both the connective portions **144a** and **144b** and the remainder of the terminals **142a** and **142b**. In such an embodiment, the terminal and the underlying conductive layer can be formed without a separate post between the two, connecting them. The terminal can include copper, or another suitable material. In some embodiments, the terminal may have a thickness of about 10 μm . The solder layers **146a** and **146b** may include tin.

[0103] **Figure 2A** is a diagram of a packaged surface acoustic wave device **200** according to an embodiment. **Figure 2B** is a detail view of section **B** of **Figure 2A**, illustrating the edge portion of the packaged surface acoustic wave device **200**. As can be seen in **Figure 2B**, the cavity walls **212** have a thickness T_w , the sidewall **226** of the conductive material **222** along the edge of the device has a thickness of T_c , and the distance from the outer edge of the sidewall **236** of the conductive material **232** to the edge of the die **202** has a thickness of T_e . In some embodiments, the thickness T_w of the cavity walls **212** is about 30 μm , the thickness T_c of the portion of the sidewall **226** of the conductive material **222** in contact with die **202** is about 15 μm , and the thickness T_e from the outer edge of the sidewall **236** of the conductive material **232** to the edge of the die **202** is about 30 μm .

[0104] **Figure 2B** illustrates that an edge portion **206** of the wafer substrate is free from the photosensitive resin forming the insulation layer **232**, such that the side **236** of the insulation layer **232** is set back from the outer edge of the die **202**. The edge portion can extend a distance in a range from about 10 μm to 20 μm from an edge of the insulation layer **232** to an edge of the die **202**. This allows the saw street area, where die

are diced and singulated, to be free from the encapsulation of the insulating layer. This in turn allows the use of a relatively thinner blade to singulate die. This can facilitate smaller spacing between adjacent die and more die on a wafer of a given size. Moreover, a thinner blade for singulation can improve reliability by reducing chipping.

[0105] **Figures 3A–3J** are cross-sections of a portion of a packaged surface acoustic wave device at various stages of a manufacturing process according to an embodiment. In the stage shown in **Figure 3A**, a die **302** is provided, including interdigital transducer electrodes **304** of one or more surface acoustic wave resonators. The die **302** may in some embodiments be a wafer with a plurality of discrete regions containing interdigital transducer electrodes which will be packaged into separate packaged surface acoustic wave devices and then separated in a singulation process. The die **302** may be a single piezoelectric layer, as shown. In other embodiments, the die **302** may be a multilayer piezoelectric substrate, including a support substrate in addition to a piezoelectric substrate. A multilayer piezoelectric substrate can include one or more additional layers along with the support substrate and the piezoelectric substrate. As one example, the support substrate can be a silicon substrate. In addition to the interdigital transducer electrodes **304**, interconnect structures extending away from the interdigital transducer electrodes **304** may also be provided on the die **302**.

[0106] In **Figure 3B**, a cavity wall **312** has been formed, circumscribing the interdigital transducer electrodes **304**. The cavity wall **312** may be a single wall with curved sections, or may include a plurality of wall segments meeting one another at angles to form a desired shape, such as a rectangle. The cavity wall **312** may include a photoresist or other photosensitive material. The height of the cavity wall **312** may correspond to a desired height of the resulting cavity. The cavity wall **312** may extend over interconnect structures supported by the die **302**, so that a portion of the interconnect structure is located outside of the cavity wall **312**. Cavity walls **312** may be formed at multiple locations across a wafer including piezoelectric material, each at a location of a package being formed.

[0107] In **Figure 3C**, a cavity roof **314** has been formed, extending from one side of the cavity wall **312** to the other side. In the illustrated embodiment, the cavity roof **314** is a planar structure with an upper surface and a lower surface extending generally parallel to one another and to the underlying surface of the die **302**. In some other embodiments, other shapes of cavity roofs may be formed, including shapes with a

recess in the lower surface of the cavity roof facing the interdigital transducer electrodes **304**. In the illustrated embodiment, the edges of the cavity roof **314** do not extend outward beyond the edges of the cavity wall **312**. This shape may facilitate deposition of subsequent materials over the cavity-defining structure.

[0108] In **Figure 3D**, a seed layer has been deposited over the outer surfaces of the cavity roof **314** and the cavity wall **320**, and a conductive layer **322** has been formed at certain locations overlying the seed layer. The conductive layer **322** includes a gap **324** between two portions of the conductive layer **322**. The conductive layer **322** also includes a sidewall portion **326** extending along the side of the cavity roof **314** and the cavity wall **312** and extending down to the die **302**.

[0109] In **Figure 3E**, exposed portions of the seed layer have been removed, and a buffer coat insulating layer **332** has been formed over the conductive layer **322**. The insulating layer **332** has apertures **334** exposing underlying sections of the conductive layer **322**. The insulation layer **332** also includes a sidewall portion **336** extending along the sides of the conductive layer **322** and down to the die **302**. The insulating layer **332** may include a negative-type photosensitive material. The insulating layer **332** may include a photosensitive resin. The insulating layer **332** may include a phenol resin with rubber filler.

[0110] In **Figure 3F**, terminals **340a** and **340b** have been formed overlying the apertures **334** in the insulation layer **332**. The terminals **340a** and **340b** fill at least part of the apertures **334** and extend over the portions of the insulation layer **332** adjacent the apertures **334**. In some embodiments, the terminals **340a** and **340b** may include copper or another suitable conductive material. The terminals **340a** and **340b** may include a layer of conformal material deposited over the apertures **334** and over the portions of the insulation layer **332** adjacent the apertures **334**, such that the terminals **340a** and **340b** include respective connecting portions **344a** and **344b** within the apertures **334** and wider upper sections **342a** and **342b** above the connecting portions **344a** and **344b**.

[0111] In **Figure 3G**, solder portions **346a** and **346b** have been formed over the upper surfaces of terminals **340a** and **340b**, respectively. The solder may include tin, in some embodiments, although other suitable solder material may be used as well. The solder portions **346a** and **346b** may facilitate bonding of the terminals **340a** and **340b** to

external devices, making connections through the conductive material **322** with the surface acoustic wave resonators within the cavity **316**.

[0112] In **Figure 3H**, the side of the die **302** opposite the interdigital transducer electrodes **304** is back ground to remove a portion **309** of the die **302** in order to reduce the thickness of the die **302** to a desired final thickness. In some embodiments, the resulting trimmed die **302'** may have an ultimate thickness of about 130 um, although other die thicknesses may also be used.

[0113] In **Figure 3I**, the side **307** of the trimmed die **302'** opposite the interdigital transducer electrodes **304** is exposed to illumination **390** from a marking laser to form marked and trimmed die **302''** having a marked portion **308**. Laser marking can be used for alignment of a module and/or for identifying a wafer and lot of a module. Laser marking can be performed directly on the piezoelectric material of trimmed die **302'** as illustrated. By marking the trimmed die **302'** directly, rather than forming an additional film or layer to be marked, the overall thickness of the resultant packaged surface acoustic wave device **300** can be reduced.

[0114] This direct marking can use illumination **390** from a deep ultraviolet laser. In one embodiment, such a laser can emit light having a wavelength that can mark a lithium-based substrate without damaging functionality of the lithium-based substrate for the surface acoustic wave device. As an example, the laser light can have a wavelength of 266 nanometers (nm). This wavelength of laser light, or a similar wavelength, can mark a lithium-based substrate, such as a lithium niobite substrate or a lithium tantalite substrate, to a relatively shallow depth, such as a depth of less than 1 micron. This shallow marking depth can prevent a significant reduction of the strength of trimmed and marked die **302''**. In addition, this wavelength of laser light should not penetrate through the lithium niobate substrate. A multilayer piezoelectric substrate can be similarly marked using suitable laser wavelengths.

[0115] **Figure 3J** shows the marked packaged surface acoustic wave device **300**, including a detail view of the marked portion **308** of the side **307** of the trimmed die **302'** opposite the interdigital transducer electrodes **304**. The detail view illustrates the markings **392** in the marked portion **308** of the underside **307** of the die **302''**. Any suitable markings, including alphanumeric markings or other symbols, may be formed. The location of the marked portion **308** may be at any suitable location or locations on the die **302''**.

[0116] The resultant packaged surface acoustic wave device **300** can have an overall package height H_I of less than 220 μm , and in certain embodiments may be less than 200 μm or approximately 190 μm . Features which reduce the overall package height H_I of device **300** include the use of a buffer coat layer to form insulation layer **332**, and the direct marking of die **302** rather than the formation and marking of a separate layer. In addition, the process illustrated in **Figures 3A–3J**, a surface acoustic wave device can be packaged with fewer processing steps (e.g., about 25 fewer) than certain previous methods.

[0117] Although **Figures 3B** and **3C** broadly illustrate the formation of cavity wall **312** and cavity roof **314**, **Figures 4A–4F** illustrate in greater detail a specific embodiment of a manufacturing process for forming a cavity wall and a cavity roof. In particular, **Figures 4A–4F** show cross-sections of a portion of a partially packaged surface acoustic wave device at various stages of a manufacturing process including multiple photoresist exposures.

[0118] **Figure 4A** shows the formation of a photosensitive layer **450** over a die **402** and interdigital transducer electrodes **404** supported by the die **402**. The die **402** and interdigital transducer electrodes **404** may be similar to the die **302** and interdigital transducer electrodes **304** of **Figure 3A**. The photosensitive layer **450** may include a photosensitive material, and may be formed having a thickness equal to the desired thickness of a cavity wall. Because the interdigital transducer electrodes **404** and other components supported by die **402** may provide an irregular upper surface on which the photosensitive layer **450** is formed, the photosensitive layer **450** may be formed by using a liquid type of photosensitive material, such as a liquid photoresin. The use of a liquid photosensitive material allows the formation of a photosensitive layer **450** of substantially constant thickness across the die **402** and over the interdigital transducer electrodes **404**.

[0119] **Figure 4B** shows the selective exposure of portions of the photosensitive layer **450** to illumination **490** using a mask **452**. In the illustrated embodiment, the photosensitive layer **450** includes a positive-type photosensitive material, where the portions of the photosensitive layer **450** to remain in the device are shielded from light, and the portions **454** of the photosensitive layer **450** to be removed are exposed to light. The masked portions of photosensitive layer **450** can remain insoluble to a photoresist developer and the unmasked portions **454** of the photosensitive layer **450** that are exposed to light can become soluble to a photoresist developer.

[0120] **Figure 4C** shows the masked portions of the photosensitive layer **450** of **Figure 4B** remaining as cavity walls **412** after removal of the unmasked portions of the photosensitive layer. This removal may include, for example, exposure of the photosensitive layer **450** to a photoresist developer to remove the soluble portions of the photosensitive layer.

[0121] In **Figure 4D**, a photoresist layer **460** has been formed over the cavity walls **412**. In contrast to the photoresist material **450** which may include a liquid type photoresin to provide a constant thickness over an irregular surface, the photoresist layer **460** may be deposited as a film supported by the cavity walls, so that a generally planar structure may be formed overlying the interdigital transducer electrodes **404** and other components supported by die **402**.

[0122] In **Figure 4E**, the photosensitive layer **460** is selectively exposed to illumination **490** using a mask **462**. In the illustrated embodiment, the photosensitive layer **460** includes a negative-type photosensitive material, where the portions of the photosensitive layer **460** to remain in the device are exposed light, and the portions **464** of the photosensitive layer **460** to be removed are shielded from light. The masked portions of photosensitive layer **450** can remain soluble to a photoresist developer and the unmasked portions **454** of the photosensitive layer **450** that are exposed to light can remain insoluble to a photoresist developer.

[0123] **Figure 4F** shows the unmasked portion of the photosensitive layer **460** of **Figure 4E** remaining as a cavity roof **414** after removal of the masked portions of the photosensitive layer. This removal may include, for example, exposure of the photosensitive layer **460** to a photoresist developer to remove the soluble portions of the photosensitive layer.

[0124] Although **Figure 3D** broadly illustrates the formation of conductive layer **322**, **Figures 5A–5F** illustrate in greater detail a specific embodiment of a manufacturing process for forming a conductive layer using a plating process. In particular, **Figures 5A–5E** are cross-sections of a portion of a partially packaged surface acoustic wave device at various stages of a manufacturing process including a plating process.

[0125] **Figure 5A** shows that a seed layer **520** has been formed over the outside surfaces of a cavity wall **512** and a cavity roof **514**. Like the partially packaged device of **Figure 4F**, the cavity wall **512** and a cavity roof **514** are supported by a die **502**

and define a cavity **516** enclosing interdigital transducer electrodes **504** supported by the die **502**. The formation of the seed layer **520** may include performing surface modification on exposed surfaces of the cavity roof **514** or other surfaces, including cleaning these surfaces. Metal can then be sputtered over the cavity roof **514** and the exposed surfaces of the cavity wall **512** to form the seed layer **520**. In some embodiments, titanium and copper can be sputtered to form a base metal for plating. The seed layer **520** may extend onto exposed portions of the die **502** adjacent the cavity walls **512**.

[0126] In **Figure 5B**, a photosensitive layer **570** has been formed over the seed layer **520**. The photosensitive layer **570** may be generally conformal over the underlying structure as shown, but in other embodiments may be thinner over the cavity roof **514** than over the die on the side. The photosensitive layer **570** may have a thickness in the area overlying the cavity roof **514** at least as thick as the eventual conductive layer to be plated onto the seed layer, so that the photosensitive layer **570** can be used to define the shape of the conductive layer to be plated onto the seed layer **520**.

[0127] In **Figure 5C**, the photosensitive layer **570** has been patterned, via selective exposure of the photosensitive layer **570** to illumination and subsequent removal of soluble portions of the photosensitive layer **570**. This removal of portions of the photosensitive layer exposes portions of the underlying seed layer **520**.

[0128] The remaining photosensitive layer portions include side portions **574** defining the edges of the conductive layer to be formed. These side portions **574** may overlie only portions of the seed layer **520** on the underlying die **502** away from the cavity walls **512**. The remaining photosensitive layer portions also include a gap-defining portion **572** extending over a portion of the cavity roof **514**. The gap-defining portion **572** may in some embodiments extend from one side portion **574** to another side portion **574**, completely separating two exposed sections of the seed layer **520** from one another. In some embodiments, additional gap-defining portions may be included to separate the exposed portions of the seed layer **520** into multiple separate sections.

[0129] In **Figure 5D**, a thicker conductive layer **522** has been plated onto the exposed portions of the seed layer **520**. The shape of the thicker conductive layer **522** is defined by the remaining portions of the photosensitive layer, including the side portions **574** and the gap-defining portion **572**. The conductive layer **522** may include copper or any other suitable material.

[0130] In **Figure 5E**, the remaining portions of the photosensitive layer, including the side portions **574** and the gap-defining portion **572**, have been removed. In addition, the exposed portions of the seed layer **520** underlying these portions of the photosensitive layer have been removed. The resulting conductive layer **522** may include discrete sections overlying the cavity roof **514**, separated by a gap **524**, as well as sidewall sections **526** extending along the sides of the cavity roof **514** and the cavity wall **512**, down to the die **502**.

[0131] Although **Figures 3E** broadly illustrates the formation of insulating layer **332**, **Figures 6A–6C** illustrate in greater detail a specific embodiment of a manufacturing process for forming an insulating layer. In particular, **Figures 6A–6C** show cross-sections of a portion of a partially packaged surface acoustic wave device at various stages of a manufacturing process including a spin-coating process.

[0132] **Figure 6A** shows that a buffer coat layer **680** has been formed over the outside surfaces of a conductive layer **622** formed over a cavity wall **612** and a cavity roof **614**. Like the partially packaged device of **Figure 5E**, the cavity wall **612** and a cavity roof **614** are supported by a die **602** and define a cavity **616** enclosing interdigital transducer electrodes **604** supported by the die **602**. In some embodiments, the buffer coat layer may include a photosensitive resin such as phenol resin. The buffer coat layer may also include a rubber filler.

[0133] In the illustrated embodiment, the thickness of the buffer coat layer **680** overlying the conductive layer **622** is thinner than the thickness of the buffer coat layer **680** overlying the die **602** away from the conductive layer **622**. The upper surface of the buffer coat layer **680** may be generally planar. In some embodiments, the buffer coat layer **680** may be deposited using a spin-coating process. The use of a spin-coating process may provide the generally planar upper surface despite the irregular profile of the underlying conductive layer **622** and die **602**. The thickness of the buffer coat layer **680** in the area overlying the cavity roof **614** may in some embodiments be less than about 10 μm , although other suitable thicknesses may also be used.

[0134] In **Figure 6B**, the buffer coat layer **680** is selectively exposed to illumination **690** using a mask **682**. In the illustrated embodiment, the buffer coat layer **680** includes a negative-type photosensitive material, where the portions of the buffer coat layer **680** to remain in the device are exposed to light, and the portions **684** of the buffer coat layer **680** to be removed are shielded from light. The masked portions **684** of

buffer coat layer **680** can remain soluble to a photoresist developer and the unmasked portions of the buffer coat layer **680** that are exposed to light can become insoluble to a photoresist developer. Broad band light may be used to expose the buffer coat layer **680**.

[0135] In **Figure 6C**, the masked portions of the buffer coat layer **680** have been removed, and the remaining portions have been cured to form an insulation layer **632** extending over the conductive layer **622**. The insulating layer **632** has apertures **634** exposing underlying sections of the conductive layer **622**. The insulation layer **632** also includes a sidewall portion **636** extending along the sides of the conductive layer **622** and down to the die **602**.

[0136] **Figure 7** is a flow diagram of a process of manufacturing a packaged surface acoustic wave device including a photosensitive buffer coat according to an embodiment. The process **700** begins at a stage **705** where a cavity structure is formed on a die supporting at least one interdigital transducer electrode. The cavity structure encapsulates the at least one interdigital transducer electrode. The formation of the cavity structure can include the formation of a cavity wall or walls surrounding the at least one interdigital transducer electrode and the formation of a cavity roof supported by the cavity walls and extending over the at least one interdigital transducer electrode.

[0137] The process **700** moves to a stage **710** where a conductive layer is formed over the cavity structure including the cavity roof and cavity wall. The conductive layer may be formed by a plating process. The plating process may include the deposition, such as via sputtering, of a seed layer, followed by plating of the conductive layer onto the seed layer. The conductive layer may include sidewall portions in contact with the die. The conductive layer may include sections which are electrically separated from one another.

[0138] The process **700** moves to a stage **715** where an insulation layer is formed over the conductive layer using a spin-coating process. The insulation layer may include a buffer coat layer. The buffer coat layer may include a phenol resin, and may include rubber filler. The insulation layer may include a negative photoresist material. The insulation layer may include a plurality of apertures exposing different portions of the conductive layer. The insulation layer may include sidewall portions in contact with the die.

[0139] The process **700** moves to a stage **720**, where a plurality of terminals are formed, each overlying and extending into an aperture in the insulation layer to

contact the conductive layer. The terminals may include copper. The terminals may include a solder layer on top of the terminal.

[0140] **Figure 8** is a flow diagram of a process of manufacturing a packaged surface acoustic wave device including laser marking of a piezoelectric layer according to an embodiment. The process **800** can be performed in combination with the process **700** in certain applications. The process **800** begins at a stage **805** where a piezoelectric substrate supporting a packaged surface acoustic wave device is provided. The packaged surface acoustic wave device may include at least one interdigital transducer electrode encapsulated within a cavity structure. The packaged surface acoustic wave device may include an insulation layer formed by a spin-on process. The insulation layer may include a negative photoresist, which may be a phenol resin, and may include rubber filler. The packaged surface acoustic wave device

[0141] The process **800** moves to a stage **810** where the piezoelectric substrate is directly laser marked. The marking process does not increase the thickness of the packaged surface acoustic wave device, as no discrete marking layer is included. The laser marking may include using a deep UV laser to mark the piezoelectric substrate. The laser making can involve applying laser light having a wavelength of 266 nm in certain instances. Such a wavelength is suitable for marking lithium niobate and/or lithium tantalate substrates. The marked portion of the piezoelectric substrate may extend less than 1 μm into the piezoelectric substrate.

[0142] The packaged surface acoustic wave devices disclosed herein can be implemented in a variety of applications, such as standalone surface acoustic wave filters, in radio frequency modules, or the like. Radio frequency modules that include packaged surface acoustic wave device in accordance with any suitable principles and advantages disclosed herein can also include one or more of a power amplifier, a radio frequency switch, a low noise amplifier, an inductor, or the like. Such radio frequency modules can benefit from reduced height and/or size of the packaged surface acoustic wave device.

[0143] **Figure 9** is a schematic diagram of a radio frequency module **900** that includes a surface acoustic wave component **1076** according to an embodiment. The illustrated radio frequency module **1200** includes the SAW component **1076** and other circuitry **1077**. The SAW component **1076** can include one or more packaged SAW filters with any suitable combination of features of the SAW packages disclosed herein.

[0144] The SAW component **1076** shown in **Figure 9** includes a filter **1078** and terminals **1079A** and **1079B**. The filter **1078** includes SAW resonators, and may be packaged in accordance with any suitable principles and advantages disclosed herein. The terminals **1079A** and **1079B** can serve, for example, as an input contact and an output contact, and may extend through a buffer coat resin insulation layer. The SAW component **1076** and the other circuitry **1077** are on or supported by a common packaging substrate **1080** in **Figure 9**. The package substrate **1080** can be a laminate substrate. The terminals **1079A** and **1079B** can be electrically connected to contacts **1081A** and **1081B**, respectively, on or supported by the packaging substrate **1080** by way of electrical connectors **1082A** and **1082B**, respectively. The electrical connectors **1082A** and **1082B** can be bumps or wire bonds, for example. The other circuitry **1077** can include any suitable additional circuitry. For example, the other circuitry can include one or more one or more power amplifiers, one or more radio frequency switches, one or more additional filters, one or more low noise amplifiers, the like, or any suitable combination thereof. The radio frequency module **1200** can include one or more packaging structures to, for example, provide protection and/or facilitate easier handling of the radio frequency module **1200**. Such a packaging structure can include an overmold structure formed over the packaging substrate **1200**. The overmold structure can encapsulate some or all of the components of the radio frequency module **1000**.

[0145] **Figure 10** is a schematic diagram of a radio frequency module **1000** that includes a packaged surface acoustic wave component according to an embodiment. As illustrated, the radio frequency module **1300** includes duplexers **1185A** to **1185N** that include respective transmit filters **1186A1** to **1186N1** and respective receive filters **1186A2** to **1186N2**, a power amplifier **1187**, a select switch **1188**, and an antenna switch **1189**. The radio frequency module **1300** can include a package that encloses the illustrated elements. The illustrated elements can be disposed on a common packaging substrate **1180**. The packaging substrate can be a laminate substrate, for example.

[0146] The duplexers **1185A** to **1185N** can each include two acoustic wave filters coupled to a common node. The two acoustic wave filters can be a transmit filter and a receive filter, and may be packaged with one another as discussed herein. As illustrated, the transmit filter and the receive filter can each be band pass filters arranged to filter a radio frequency signal. A packaged SAW device in accordance with any suitable principles and advantages disclosed herein can include one or more SAW

resonators of one or more of the transmit filters **1186A1** to **1186N1** and/or one or more of the receive filters **1186A2** to **1186N2**. Although **Figure 10** illustrates duplexers, any suitable principles and advantages disclosed herein can be implemented in other multiplexers (e.g., quadplexers, hexaplexers, octoplexers, etc.) and/or in switch-plexers.

[0147] The power amplifier **1187** can amplify a radio frequency signal. The illustrated switch **1188** is a multi-throw radio frequency switch. The switch **1188** can electrically couple an output of the power amplifier **1187** to a selected transmit filter of the transmit filters **1186A1** to **1186N1**. In some instances, the switch **1188** can electrically connect the output of the power amplifier **1187** to more than one of the transmit filters **1186A1** to **1186N1**. The antenna switch **1189** can selectively couple a signal from one or more of the duplexers **1185A** to **1185N** to an antenna port ANT. The duplexers **1185A** to **1185N** can be associated with different frequency bands and/or different modes of operation (e.g., different power modes, different signaling modes, etc.).

[0148] **Figure 11** is a schematic block diagram of a module **1210** that includes a power amplifier **1212**, a radio frequency switch **1214**, and duplexers **1291A** to **1291N** in accordance with one or more embodiments. The power amplifier **1212** can amplify a radio frequency signal. The radio frequency switch **1214** can be a multi-throw radio frequency switch. The radio frequency switch **1214** can electrically couple an output of the power amplifier **1212** to a selected transmit filter of the duplexers **1291A** to **1291N**. A packaged SAW device in accordance with any suitable principles and advantages disclosed herein can include one or more SAW resonators of one or more filters of the duplexers **1291A** to **1291N** and/or one or more of duplexers **1291A** to **1291N**.

[0149] **Figure 12** is a schematic block diagram of a module **1270** that includes filters **1271A** to **1271N**, a radio frequency switch **1274**, and a low noise amplifier **1272** according to an embodiment. A packaged SAW device in accordance with any suitable principles and advantages disclosed herein can include one or more SAW resonators of one or more filters of the filters **1271A** to **1271N**. Some or all of the filters may be packaged as discussed herein. Any suitable number of filters **1271A** to **1271N** can be implemented. The illustrated filters **1271A** to **1271N** are receive filters. In some embodiments (not illustrated), one or more of the filters **1271A** to **1271N** can be included in a multiplexer that also includes a transmit filter. The radio frequency switch **1274** can be a multi-throw radio frequency switch. The radio frequency switch **1274** can

electrically couple an output of a selected filter of filters **1271A** to **1271N** to the low noise amplifier **1272**. In some embodiments (not illustrated), a plurality of low noise amplifiers can be implemented. The module **1270** can include diversity receive features in certain applications.

[0150] **Figure 13** is a schematic block diagram of a module **1395** that includes duplexers **1391A** to **1391N** and an antenna switch **1394**. One or more filters of the duplexers **1391A** to **1391N** can be packaged as described herein and may include any suitable number of surface acoustic wave resonators, in accordance with any suitable principles and advantages discussed herein. Any suitable number of duplexers **1391A** to **1391N** can be implemented. The antenna switch **1394** can have a number of throws corresponding to the number of duplexers **1391A** to **1391N**. The antenna switch **1394** can electrically couple a selected duplexer to an antenna port of the module **1395**.

[0151] **Figure 14** is a schematic diagram of a wireless communication device **1400** that includes filters **1403** in a radio frequency front end **1402** according to an embodiment. The filters **1403** can include one or more SAW resonators in accordance with any suitable principles and advantages discussed herein. The wireless communication device **1400** can be any suitable wireless communication device. For instance, a wireless communication device **1400** can be a mobile phone, such as a smart phone. As illustrated, the wireless communication device **1400** includes an antenna **1401**, an RF front end **1402**, a transceiver **1404**, a processor **1405**, a memory **1406**, and a user interface **1407**. The antenna **1401** can transmit RF signals provided by the RF front end **1402**. Such RF signals can include carrier aggregation signals. Although not illustrated, the wireless communication device **1400** can include a microphone and a speaker in certain applications.

[0152] The RF front end **1402** can include one or more power amplifiers, one or more low noise amplifiers, one or more RF switches, one or more receive filters, one or more transmit filters, one or more duplex filters, one or more multiplexers, one or more frequency multiplexing circuits, the like, or any suitable combination thereof. The RF front end **1402** can transmit and receive RF signals associated with any suitable communication standards. The filters **1403** may be packaged with one another, or with a subset of the filters **1403**, and can include packaged SAW devices including any suitable combination of features discussed with reference to any embodiments discussed herein.

[0153] The transceiver **1404** can provide RF signals to the RF front end **1402**

for amplification and/or other processing. The transceiver **1404** can also process an RF signal provided by a low noise amplifier of the RF front end **1402**. The transceiver **1404** is in communication with the processor **1405**. The processor **1405** can be a baseband processor. The processor **1405** can provide any suitable base band processing functions for the wireless communication device **1400**. The memory **1406** can be accessed by the processor **1405**. The memory **1406** can store any suitable data for the wireless communication device **1400**. The user interface **1407** can be any suitable user interface, such as a display with touch screen capabilities.

[0154] **Figure 15** is a schematic diagram of a wireless communication device **1510** that includes filters **1503** in a radio frequency front end **1502** and second filters **1513** in a diversity receive module **1512**. The wireless communication device **1510** is like the wireless communication device **1500** of **Figure 14**, except that the wireless communication device **1520** also includes diversity receive features. As illustrated in **Figure 15**, the wireless communication device **1520** includes a diversity antenna **1511**, a diversity module **1512** configured to process signals received by the diversity antenna **1511** and including filters **1513**, and a transceiver **1504** in communication with both the radio frequency front end **1502** and the diversity receive module **1512**. The filters **1513** may be packaged with one another, or with a subset of the filters **1513**, and can include packaged SAW devices including any suitable combination of features discussed with reference to any embodiments discussed herein.

[0155] Any suitable principles and advantages of the surface acoustic wave devices disclosed herein can be implemented with one or more temperature compensated SAW resonators. Temperature compensated SAW resonators include a temperature compensation layer (e.g., a silicon dioxide layer) over an interdigital transducer electrode to bring a temperature coefficient of frequency closer to zero.

[0156] Packaged surface acoustic wave devices disclosed herein can include one or more surface acoustic wave resonators included in a filter arranged to filter a radio frequency signal in a fourth generation (4G) Long Term Evolution (LTE) operating band. Packaged surface acoustic wave devices disclosed herein can include one or more surface acoustic wave resonators included in a filter arranged to filter a radio frequency signal in a fifth generation (5G) New Radio (NR) operating band within Frequency Range 1 (FR1). FR1 can be from 410 megahertz (MHz) to 7.125 gigahertz (GHz), for example, as specified in a current 5G NR specification. Packaged surface acoustic wave devices

disclosed herein can include one or more surface acoustic wave resonators included in a filter with a passband corresponding to both a 4G LTE operating band and a 5G NR operating band within FR1.

[0157] Any of the embodiments described above can be implemented in association with a radio frequency system and/or mobile devices such as cellular handsets. The principles and advantages of the embodiments can be used for any systems or apparatus that could benefit from any of the embodiments described herein. The teachings herein are applicable to a variety of systems. Although this disclosure includes example embodiments, the teachings described herein can be applied to a variety of structures. Any of the principles and advantages discussed herein can be implemented in association with RF circuits configured to process signals in a frequency range from about 30 kHz to 300 GHz, such as in a frequency range from about 450 MHz to 8.5 GHz.

[0158] Aspects of this disclosure can be implemented in various electronic devices. Examples of the electronic devices can include, but are not limited to, consumer electronic products, parts of the consumer electronic products such as semiconductor die and/or packaged radio frequency modules, electronic test equipment, uplink wireless communication devices, personal area network communication devices, etc. Examples of the consumer electronic products can include, but are not limited to, a mobile phone such as a smart phone, a wearable computing device such as a smart watch or an ear piece, a telephone, a television, a computer monitor, a computer, a router, a modem, a hand-held computer, a laptop computer, a tablet computer, a personal digital assistant (PDA), a microwave, a refrigerator, a vehicular electronics system such as an automotive electronics system, a stereo system, a DVD player, a CD player, a digital music player such as an MP3 player, a radio, a camcorder, a camera such as a digital camera, a portable memory chip, a washer, a dryer, a washer/dryer, a peripheral device, a clock, etc. Further, the electronic devices can include unfinished products.

[0159] Unless the context clearly requires otherwise, throughout the description and the claims, the words “comprise,” “comprising,” “include,” “including” and the like are to be construed in an inclusive sense, as opposed to an exclusive or exhaustive sense; that is to say, in the sense of “including, but not limited to.” The word “coupled”, as generally used herein, refers to two or more elements that may be either directly connected, or connected by way of one or more intermediate elements. Likewise, the word “connected”, as generally used herein, refers to two or more elements that may

be either directly connected, or connected by way of one or more intermediate elements. Additionally, the words “herein,” “above,” “below,” and words of similar import, when used in this application, shall refer to this application as a whole and not to any particular portions of this application. Where the context permits, words in the above Detailed Description using the singular or plural number may also include the plural or singular number respectively. The word “or” in reference to a list of two or more items, that word covers all of the following interpretations of the word: any of the items in the list, all of the items in the list, and any combination of the items in the list.

[0160] Moreover, conditional language used herein, such as, among others, “can,” “could,” “might,” “may,” “e.g.,” “for example,” “such as” and the like, unless specifically stated otherwise, or otherwise understood within the context as used, is generally intended to convey that certain embodiments include, while other embodiments do not include, certain features, elements and/or states. Thus, such conditional language is not generally intended to imply that features, elements and/or states are in any way required for one or more embodiments or that one or more embodiments necessarily include logic for deciding, with or without author input or prompting, whether these features, elements and/or states are included or are to be performed in any particular embodiment.

[0161] While certain embodiments have been described, these embodiments have been presented by way of example only, and are not intended to limit the scope of the disclosure. Indeed, the novel apparatus, methods, and systems described herein may be embodied in a variety of other forms; furthermore, various omissions, substitutions and changes in the form of the methods and systems described herein may be made without departing from the spirit of the disclosure. For example, while blocks are presented in a given arrangement, alternative embodiments may perform similar functionalities with different components and/or circuit topologies, and some blocks may be deleted, moved, added, subdivided, combined, and/or modified. Each of these blocks may be implemented in a variety of different ways. Any suitable combination of the elements and acts of the various embodiments described above can be combined to provide further embodiments. The accompanying claims and their equivalents are intended to cover such forms or modifications as would fall within the scope and spirit of the disclosure.

WHAT IS CLAIMED IS:

1. A packaged surface acoustic wave device comprising:
a cavity roof over an interdigital transducer electrode of a surface acoustic wave device;
a conductive structure over the cavity roof; and
a photosensitive buffer coat layer over the conductive structure, the packaged surface acoustic wave device having a height of 220 micrometers or less.
2. The packaged surface acoustic wave device of claim 1 wherein the packaged surface acoustic wave device has a height of 200 micrometers or less.
3. The packaged surface acoustic wave device of claim 1 wherein the photosensitive buffer coat layer has a height of 15 micrometers or less.
4. The packaged surface acoustic wave device of claim 1 further comprising a piezoelectric substrate having a first side on which the interdigital transducer electrode is disposed, and a cavity wall on the first side of the piezoelectric substrate and supporting the cavity roof.
5. The packaged surface acoustic wave device of claim 4 wherein an edge portion of the first side of the piezoelectric substrate is free from the photosensitive buffer coat layer.
6. The packaged surface acoustic wave device of claim 1 further comprising a piezoelectric substrate having a first side and a second side opposite the first side, the interdigital transducer electrode being on the first side, and a marking extending into the second side, the marking extending 1 micrometer or less into the piezoelectric substrate.
7. The packaged surface acoustic wave device of claim 1 further comprising a terminal in physical contact with the conductive structure through an opening in the photosensitive buffer coat layer.

8. The packaged surface acoustic wave device of claim 1 wherein the photosensitive buffer coat layer includes phenol resin.

9. The packaged surface acoustic wave device of claim 1 wherein the photosensitive buffer coat layer has a negative photosensitivity.

10. The packaged surface acoustic wave device of claim 1 wherein the surface acoustic wave device includes a plurality of surface acoustic wave resonators configured to filter a radio frequency signal.

11. A packaged surface acoustic wave device comprising:
a cavity structure supported by a die and cooperating the die to encapsulate an interdigital transducer electrode of a surface acoustic wave device;
a conductive structure extending over a portion of an outer surface of the cavity structure; and
an insulating layer extending over the conductive structure, a portion of the insulating layer overlying a portion of the conductive structure having a thickness of less than 15 micrometers.

12. The packaged surface acoustic wave device of claim 11 wherein the cavity structure includes a cavity wall supported by a first surface of the die and a cavity roof extending over the interdigital transducer electrode and supported by the cavity wall.

13. The packaged surface acoustic wave device of claim 12 further comprising a plurality of terminals, each of the terminals extending through a portion of the insulating layer and contacting a portion of the conductive structure.

14. The packaged surface acoustic wave device of claim 11 wherein the insulating layer includes a photoresist material.

15. The packaged surface acoustic wave device of claim 14 wherein the insulating layer includes a negative photoresist.

16. The packaged surface acoustic wave device of claim 14 wherein the die comprises a laser-marked piezoelectric substrate having a first side and a second side, the first side supporting the cavity structure, the second side of the laser-marked piezoelectric substrate having a laser-marked section.

17. A packaged surface acoustic wave device comprising:

a piezoelectric substrate;

a packaging structure supported by a first surface of the piezoelectric substrate and defining a cavity, the packaging structure including an outer layer including photosensitive resin; and

a plurality of interdigital transducer electrodes supported by the piezoelectric substrate and located within the cavity.

18. The packaged surface acoustic wave device of claim 17 wherein the packaging structure includes a cavity roof and a cavity wall, the cavity roof and the cavity wall both located between a portion of the outer layer and the plurality of interdigital transducer electrodes.

19. The packaged surface acoustic wave device of claim 17 wherein the packaging structure includes a conductive structure in electrical communication with at least one of the plurality of interdigital transducer electrodes.

20. The packaged surface acoustic wave device of claim 19 wherein the packaging structure includes at least one terminal overlying a portion of the outer layer and extending through a portion of the outer layer to contact the conductive structure.

21. A method of manufacturing a packaged surface acoustic wave device, the method comprising:

forming a photosensitive resin over a conductive structure, a portion of the conductive structure located over a cavity roof over an interdigital transducer electrode of the surface acoustic wave device; and

forming a conductive terminal in contact with the conductive structure, at least a portion of the conductive terminal extending through an aperture extending through the photosensitive resin.

22. The method of claim 21 further comprising exposing portions of the photosensitive resin to light to develop portions of the photosensitive resin and removing unexposed portions of the photosensitive resin.

23. The method of claim 22 further comprising curing the photosensitive resin after removing unexposed portions of the photosensitive resin.

24. The method of claim 22 wherein the exposing portions of the photosensitive resin to light includes masking a portion of the photosensitive resin extending over a portion of the conductive structure to form the aperture extending through the photosensitive resin.

25. The method of claim 21 wherein the forming the terminal includes forming a conductive layer extending over the aperture extending through the photosensitive resin.

26. The method of claim 21 wherein the aperture extends through a portion of the photosensitive resin having a thickness of 15 micrometers or less.

27. The method of claim 21 wherein the photosensitive resin includes phenol resin.

28. The method of claim 21 further comprising laser marking a piezoelectric substrate on which the interdigital transducer electrode is disposed.

29. The method of claim 21 wherein the packaged surface acoustic wave device has a height of less than 220 micrometers.

30. A method of manufacturing a packaged surface acoustic wave device, the method comprising:

forming a cavity structure encapsulating interdigital transducer electrodes of a surface acoustic wave device, the interdigital transducer electrodes supported by a piezoelectric substrate;

forming a conductive structure extending over portions of an outer surface of the cavity structure; and

forming a photoresist layer over the conductive structure, a portion of the photoresist layer extending over a portion of the conductive structure having a thickness of less than 15 micrometers.

31. The method of claim 30 further comprising patterning the photoresist layer to form a photoresist buffer coat extending over the conductive structure and the cavity structure and curing the photoresist layer.

32. The method of claim 31 wherein the photoresist buffer coat includes a sidewall portion in contact with the piezoelectric substrate and circumscribing the cavity structure.

33. The method of claim 32 wherein a portion of the conductive structure is in contact with the piezoelectric substrate.

34. The method of claim 30 wherein the forming the photoresist layer over the conductive structure includes using a spin-on process to planarize the photoresist layer.

35. The method of claim 30 further comprising removing portions of the photoresist layer within 10 micrometers of the edge of the die.

36. A method of manufacturing a packaged surface acoustic wave device, the method comprising:

forming a cavity structure extending over interdigital transducer electrodes of the surface acoustic wave device;

forming a conductive structure extending over portions of an outer surface of the cavity structure; and

forming a photosensitive resin layer over the conductive structure, a portion of the photosensitive resin layer having an aperture extending therethrough and exposing a portion of the conductive structure.

37. The method of claim 36 wherein the forming the conductive structure includes depositing a seed layer over the cavity structure and plating the conductive structure onto the seed layer.

38. The method of claim 37 wherein the forming the conductive structure further includes masking portions of the seed layer prior to plating the conductive structure onto the seed layer.

39. The method of claim 36 wherein the conductive structure includes a gap extending through a portion thereof and exposing a portion of the cavity structure, and the photosensitive resin layer fills the gap.

40. The method of claim 36 further comprising forming a conductive terminal extending through an aperture in the photosensitive resin layer and in electrical communication with the conductive structure.

41. A packaged surface acoustic wave device comprising:
a piezoelectric substrate having a first side and a second side;
an interdigital transducer electrode encapsulated within a package structure and supported by the first side of the piezoelectric substrate; and
a marking formed in the second side of the piezoelectric substrate.

42. The packaged surface acoustic wave device of claim 41 wherein the marking extends less than 1 micrometer into the second side of the piezoelectric substrate.

43. The packaged surface acoustic wave device of claim 41 wherein the marking extends less into less than 1% of a thickness of the piezoelectric substrate.

44. The packaged surface acoustic wave device of claim 41 wherein the marking is formed by a laser.

45. The packaged surface acoustic wave device of claim 41 wherein the piezoelectric substrate includes lithium niobate.

46. The packaged surface acoustic wave device of claim 41 wherein the piezoelectric substrate includes lithium tantalite.

47. The packaged surface acoustic wave device of claim 41 wherein the package structure includes a cavity structure encapsulating the interdigital transducer electrode and an outer coat including a photosensitive resin.

48. The packaged surface acoustic wave device of claim 41 wherein a total thickness of the packaged surface acoustic wave device is less than 220 micrometers.

49. The packaged surface acoustic wave device of claim 41 wherein the package structure includes a photosensitive resin buffer coat.

50. The packaged surface acoustic wave device of claim 49 wherein the photosensitive resin buffer coat includes phenol resin.

51. The packaged surface acoustic wave device of claim 49 wherein the photosensitive resin buffer coat includes a negative photoresist.

52. The packaged surface acoustic wave device of claim 49 further comprising a plurality of terminals extending through apertures in the photosensitive resin buffer coat.

53. A packaged surface acoustic wave device comprising:

- a laser-marked piezoelectric substrate having a first side and a second side, the second side of the laser-marked piezoelectric substrate having a laser-marked section;

- an interdigital transducer electrode supported by the first side of the laser-marked piezoelectric substrate, and

- a structure supported by the first side of the laser-marked piezoelectric substrate defining a cavity enclosing the interdigital transducer electrode.

54. The packaged surface acoustic wave device of claim 53 wherein the laser-marked section has been exposed to a deep ultraviolet laser.

55. The packaged surface acoustic wave device of claim 53 wherein the laser-marked section includes laser markings extending less than 1 micrometer into the second side of the piezoelectric substrate.

56. The packaged surface acoustic wave device of claim 53 wherein the laser-marked piezoelectric substrate includes lithium niobate.

57. The packaged surface acoustic wave device of claim 53 wherein the laser-marked piezoelectric substrate includes lithium tantalite.

58. The packaged surface acoustic wave device of claim 53 wherein the package structure includes a photosensitive resin buffer coat.

59. The packaged surface acoustic wave device of claim 58 wherein the photosensitive resin buffer coat includes phenol resin.

60. The packaged surface acoustic wave device of claim 58 wherein the photosensitive resin buffer coat includes a negative photoresist.

61. A method of marking a packaged surface acoustic wave device, the method comprising:

grinding a back side of a piezoelectric substrate, the back side being opposite a front side of the piezoelectric substrate on which an interdigital transducer electrode of the surface acoustic wave device is disposed; and
laser marking the piezoelectric substrate.

62. The method of claim 61 wherein the laser marking forms a marking that extends less than 1 micron into the piezoelectric substrate.

63. The method of claim 61 wherein the laser marking includes applying a wavelength of laser light that allows the piezoelectric substrate to maintain structural integrity.

64. The method of claim 61 wherein the laser marking includes using a deep ultraviolet laser.

65. The method of claim 61 wherein the laser marking includes using a laser with a wavelength of about 266 nanometers.

66. The method of claim 61 wherein the grinding the back side of the piezoelectric substrate includes grinding the back side of the piezoelectric substrate until a thickness of the piezoelectric substrate is about 130 micrometers.

67. The method of claim 61 wherein the piezoelectric substrate includes lithium niobate.

68. The method of claim 61 wherein the piezoelectric substrate includes lithium tantalite.

69. The method of claim 61 further comprising forming a structure supported by the front side of the piezoelectric substrate and defining a cavity enclosing the interdigital transducer electrode.

70. The method of claim 69 wherein the structure supported by the front side of the piezoelectric substrate is formed before grinding the back side of the piezoelectric substrate.

71. The method of claim 69 wherein forming the structure supported by the front side of the piezoelectric substrate includes forming a photosensitive resin buffer coat.

72. A method of marking a packaged surface acoustic wave device, the method comprising:

forming a packaging structure on a first surface of a piezoelectric substrate on which an interdigital transducer electrode of the surface acoustic wave device

is disposed, the packaging structure encapsulating the interdigital transducer electrode in a cavity; and

directly marking a second surface of the piezoelectric substrate to form a marked portion of the piezoelectric substrate.

73. The method of claim 72 wherein the directly marking the second surface of the piezoelectric substrate includes exposing the marked portion of the second surface of the piezoelectric substrate to laser light.

74. The method of claim 73 wherein the laser light includes deep ultraviolet light.

75. The method of claim 73 wherein the laser light has a wavelength of about 266 nanometers.

76. The method of claim 72 wherein the forming a packaging structure includes forming a layer of photosensitive resin and patterning the layer of photosensitive resin.

77. The method of claim 76 wherein the photosensitive resin includes a phenol resin.

78. The method of claim 76 wherein the forming a packaging structure includes forming a conductive terminal extending through the layer of photosensitive resin.

79. The method of claim 72 wherein the marking extends less than 1 micron into the piezoelectric substrate.

80. The method of claim 72 wherein the packaged surface acoustic wave device has a thickness of less than 220 micrometers.